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Negative type photosensitive compsn., for photoresist, etc. - contains water insol. and alkali soluble resin, acid generating cpd., cpd. capable of crosslinking and base generating cpd. and has high sensitivity and resolution

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Patent Family:

Patent No	Kind	Date	Applicat No	Kind	Date	Week
JP 5158239	A	19930625	JP 91344085	A	19911203	199330 B
US 5576143	A	19961119	US 92985262	A	19921203	199701

Priority Applications (No Type Date): JP 91344085 A 19911203; JP 91344112 A 19911203

Patent Details:

Patent No	Kind	Lan	Pg	Main IPC	Filing Notes
JP 5158239	A	31		G03F-007/038	
US 5576143	A	19		G03C-001/492	

Abstract (Basic): JP 5158239 A

Compsn. contains: (A) a resin which is water insoluble and alkali soluble; (B) a cpd. which generates an acid due to the irradiation of active rays or radiation; (C) a cpd. which has at least one gp. capable of crosslinking due to the effect of an acid, and (D) a cpd. which generates a base at more than 50 deg.C.

USE/ADVANTAGE - This photosensitive compsn. has high sensitivity and resolution. This compsn. is intended for use as a photoresist, esp., it is best fit for a micro-photoresist. Typically, it is used for a lithographic printing plate and the photoresist obtd. from this compsn. is not affected by varying conditions of processing after the exposure. It is fit for a light source having a short wavelength of a Deep-UV area

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